

PATENT NUMBER

SCANNED <u>IKI</u> Q.A. <u>AM</u>	O.I.P.E.	PATENT DATE
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APPLICATION NO. 09/905172	CONT/PRIOR D	CLASS 438	SUBCLASS 710	ART UNIT 1765	EXAMINER WBC
<p>APPLICANTS</p> <p>David Mui Wei Liu Thorsten Lill Christopher Bencher</p>					
<p>TITLE</p> <p>Etch pattern definition using a CVD organic layer as an anti-reflection coating and hardmask</p>					

PTO-2040
12/99

[illegible]

<input type="checkbox"/> TERMINAL DISCLAIMER	DRAWINGS		CLAIMS ALLOWED	
	Sheets Drwg.	Figs. Drwg.	Print Fig.	Total Claims
<input type="checkbox"/> The term of this patent subsequent to _____ (date) has been disclaimed. <input type="checkbox"/> The term of this patent shall not extend beyond the expiration date of U.S. Patent No. _____ <input type="checkbox"/> The terminal _____ months of this patent have been disclaimed.	_____ (Assistant Examiner) _____ (Date)		NOTICE OF ALLOWANCE MAILED	
	_____ (Primary Examiner) _____ (Date)		ISSUE FEE	
			Amount Due	Date Paid
	_____ (Legal Instruments Examiner) _____ (Date)		ISSUE BATCH NUMBER	
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